

Application No. 09/449,907
Attorney Docket No. 107176-09004

the workpiece for polishing the same and disposed in a first plane;

polishing agent passages, having bottoms disposed in a second plane, for introducing a polishing agent; and

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a plurality of one-stage step portions formed between said polishing faces of said polishing projections and the bottoms of said polishing agent passages and disposed in a third plane, the first, second and third planes spaced apart from and extending parallel to one another.

5A. (Once Amended) A chemical mechanical polishing apparatus, comprising:

a chemical mechanical polishing cloth for chemically mechanically polishing a workpiece;

a polishing head for holding and rubbing a workpiece with said chemical mechanical polishing cloth; and

a polishing agent supply mechanism for supplying a polishing agent to said chemical mechanical polishing cloth,

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said chemical mechanical polishing cloth including, on an opposite-to-workpiece face thereof:

polishing projections having polishing faces arranged to come in contact with the workpiece for polishing the same and disposed in a first plane;

polishing agent passages, having bottoms disposed in a second plane, for introducing a polishing agent; and

a plurality of one-stage step portions formed between said polishing faces of said polishing projections and the bottoms of said polishing agent passages and